



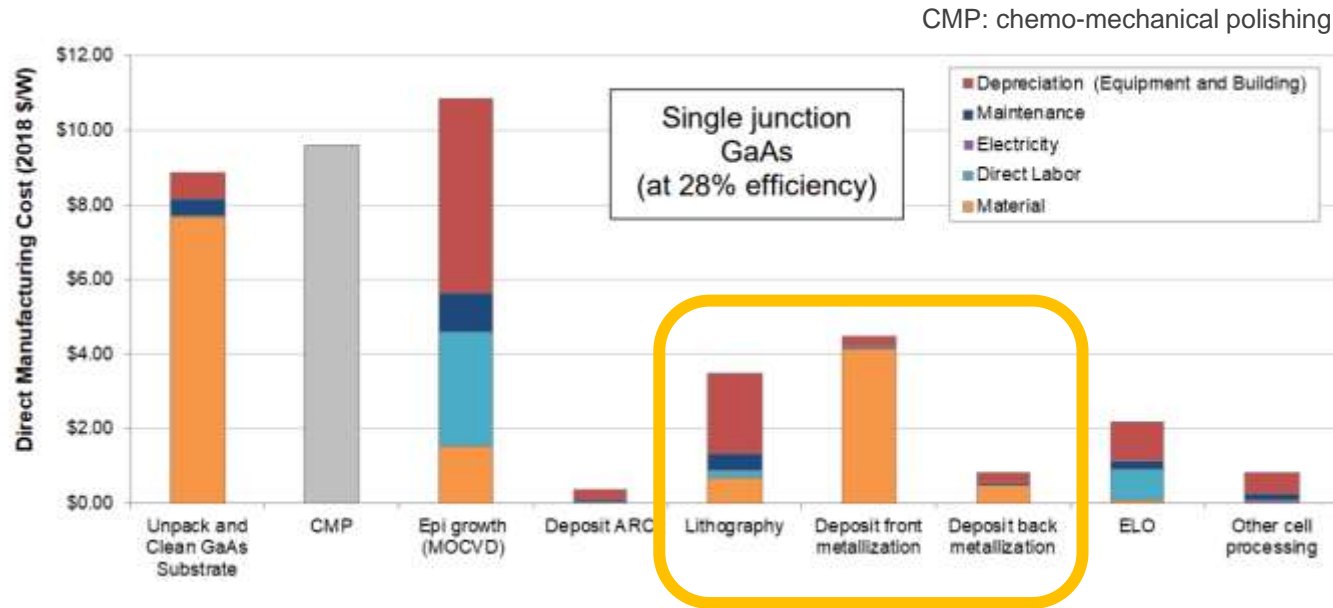
School of Photovoltaic and Renewable Energy Engineering

Can Copper be an alternative strategy of front contact for GaAs-based III-V solar cells?

Mengdi Liu, Udo Roemer, Alison Lennon, N.J. Ekins-Daukes

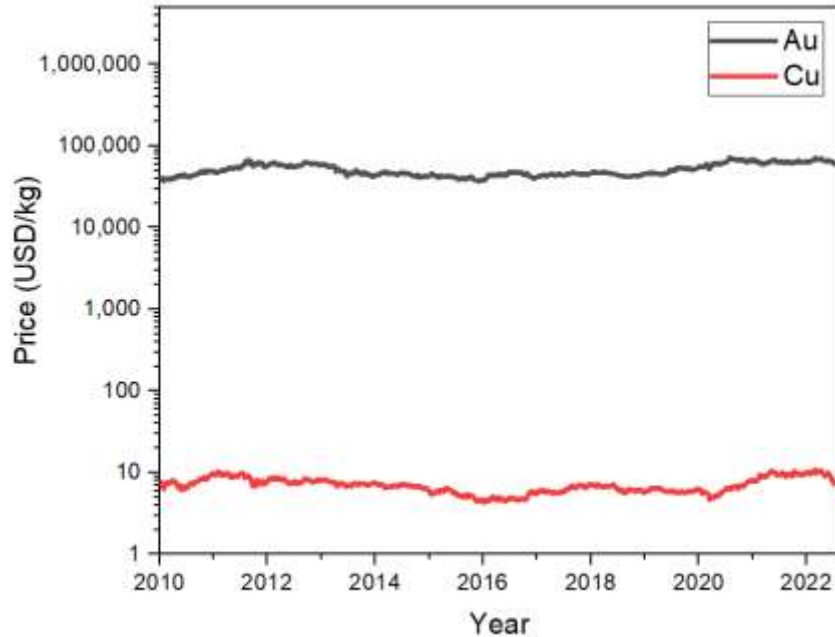
7 December 2023

Background



- Front metallization costs: about US\$ 4/Wdc, **10% of total costs**.
- Prevailing metallization approaches have prioritized performance over cost.

Copper?



- **High conductivity** ($5.8 \times 10^7 \text{ S m}^{-1}$) ;
- **Low material cost** (below US\$10/kg) ;
- **Low processing cost** (plating);
- US\$4.00/ Wdc \rightarrow US\$0.07/ Wdc

- **Fast diffuser** in GaAs (diffusion coefficient $10^{-9} \text{ cm}^2/\text{s}$ at 100°C);
- Introduce **trap levels** in the bandgap;
- **Limited** researches on Cu-plating technology for III-Vs;

[2] "Gold Prices - 100 Year Historical Chart." macrotrends.

[3] "Copper Prices - 45 Year Historical Chart." macrotrends.

[4] M. Woodhouse and A. Goodrich, National Renewable Energy Lab (NREL), 2013.

Motivation

Reducing the **metallisation costs** of III-V solar cells but without sacrificing efficiencies

- Improved understanding of the metallurgy associated with the different interfaces in Cu-plated contacts;
- Demonstrations of industrially-feasible Cu-plated metallisation processes.

Outlines

- I. Copper diffusion barrier layer investigation;
- II. Copper plating development.

Accelerated Ageing Test

- Temperature-depend diffusion $(D = D_0 \exp(-E_a/kT))$
- Temperature accelerated tests: $\frac{t_{op}}{t_{acc}} = \exp\left[\frac{E_a}{k}\left(\frac{1}{T_{op}} - \frac{1}{T_{acc}}\right)\right]$
 - Arrhenius law
 - Activation energy E_a ranging from 0.9-1.5eV for CPV III-V solar cells

$E_a=0.9\text{eV}$

T_{acc}	t_{acc}	T_{op}	t_{op}	If assuming 5h per day
300 °C	0.5 h	80 °C	42559.3 h	23.3 years
300 °C	0.5 h	110 °C	4200.9 h	2.30 years

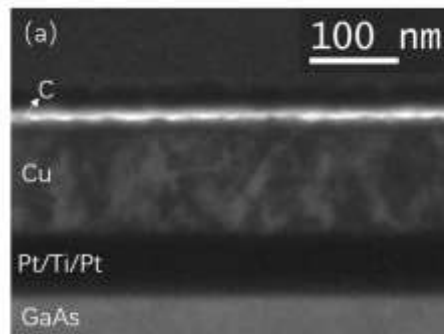
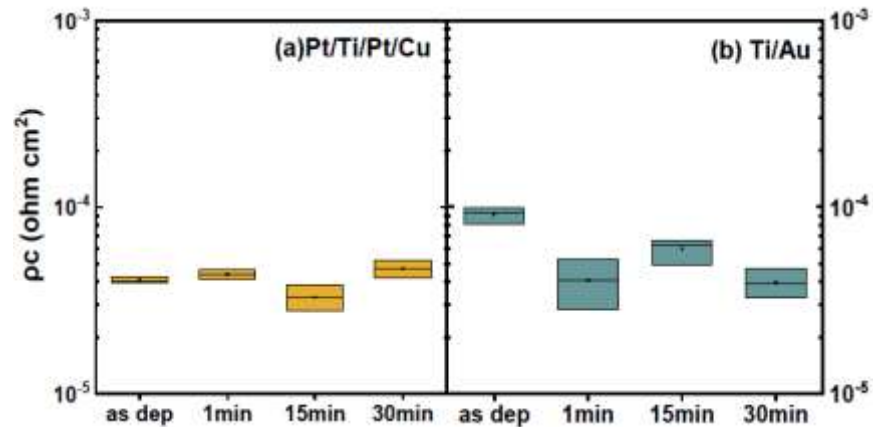
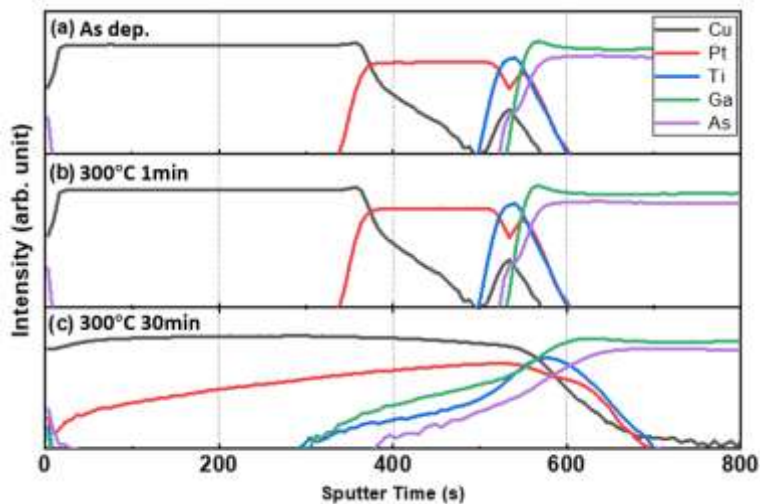
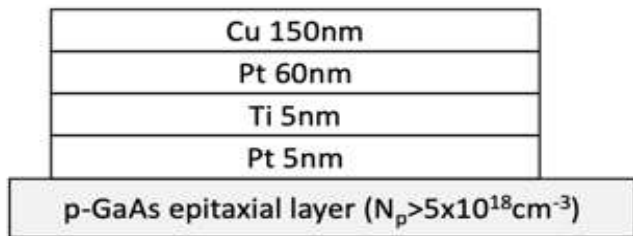
acc: accelerated condition op: operating condition

Copper Barriers

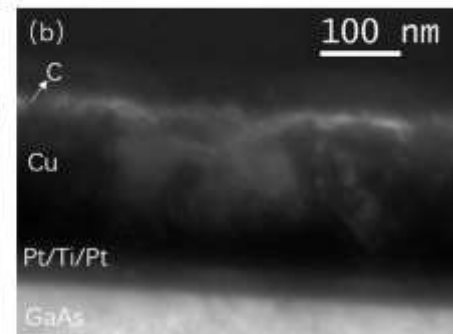
- Barrier performance qualification conditions: no heavy Cu penetration after annealing at 300 °C for 30min;
- Deposition method: e-beam evaporation.

Structure	
n-GaAs	Pd10nm/Ge150nm/Cu 150nm
p-GaAs	Pt 5nm/Ti10nm/Pt 60nm/Cu 150nm

For p-GaAs

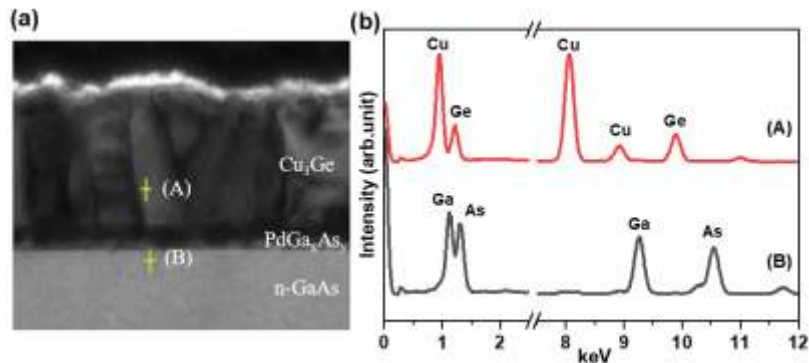
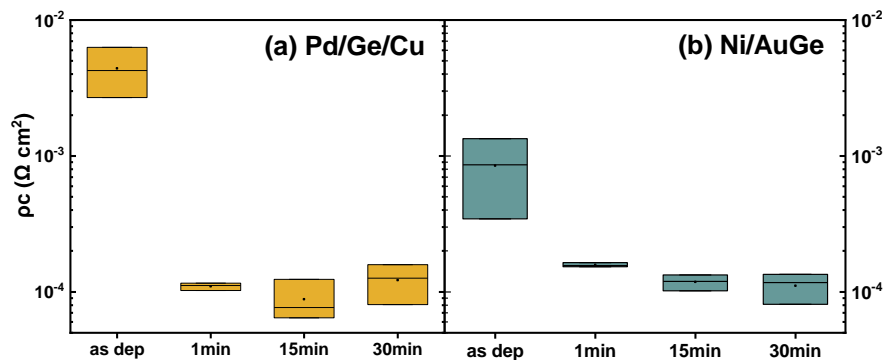
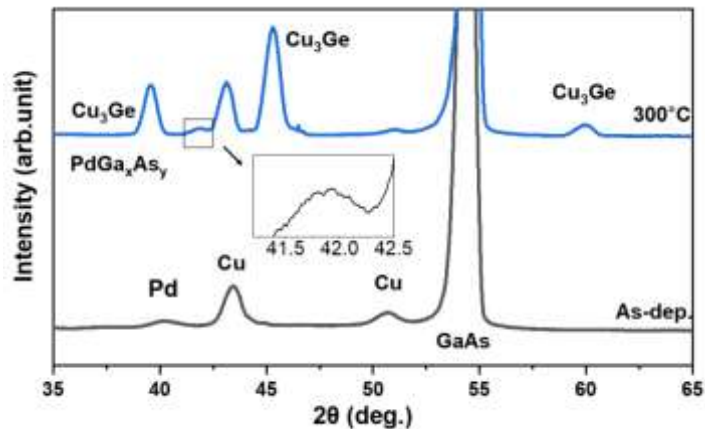
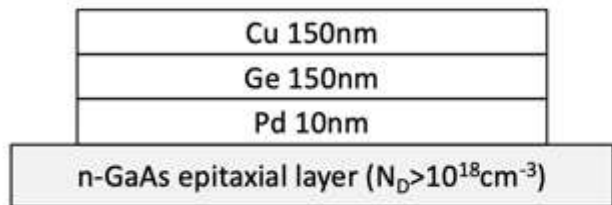


300°C 1min

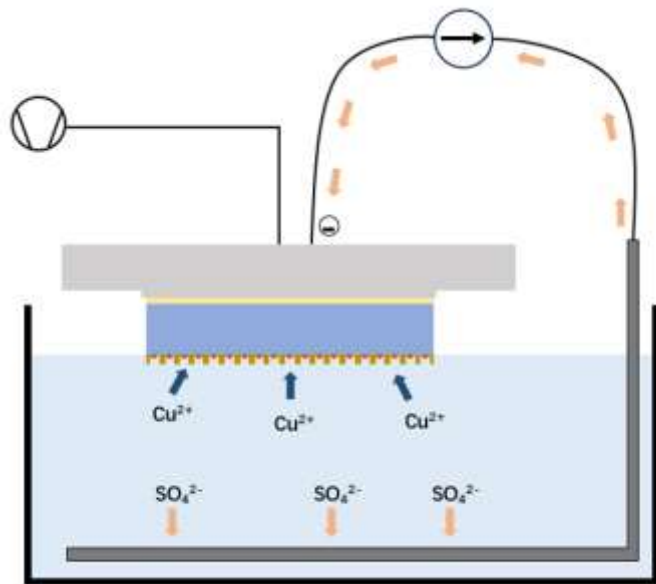









300°C 30min

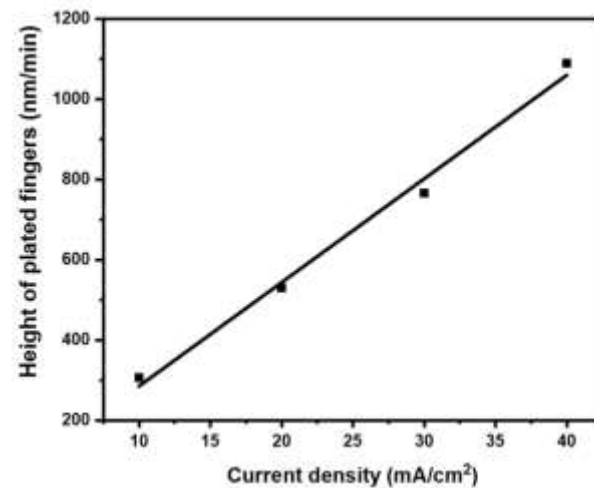
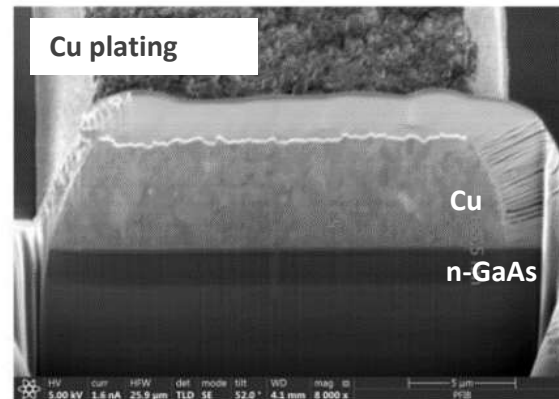
For n-GaAs



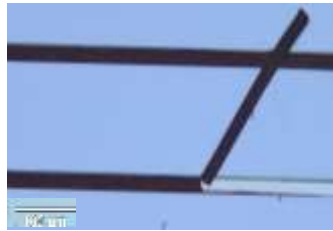
Copper Plating



-  Cu anode
-  Cathode (ohmic contact layer)
-  Photoresist
-  III-V
-  Rear side metallization
-  Holder
-  Vacuum pump



Voids Control

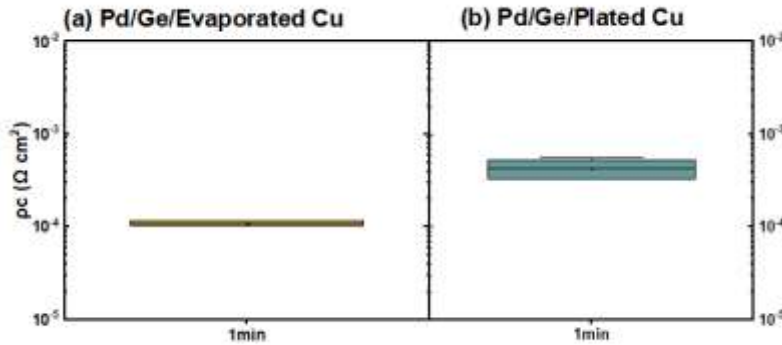
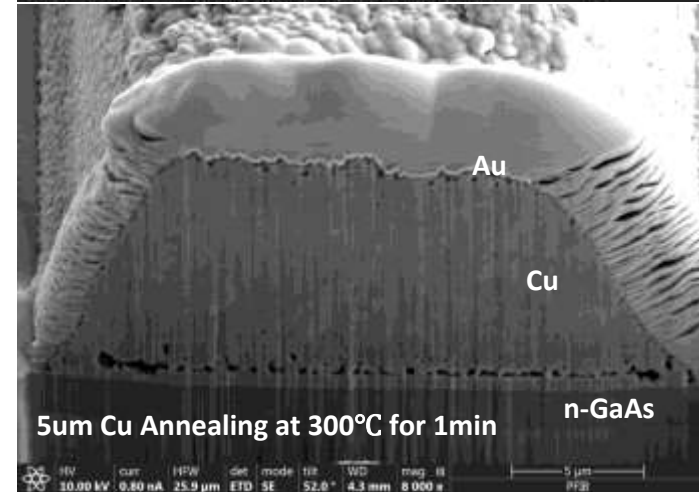
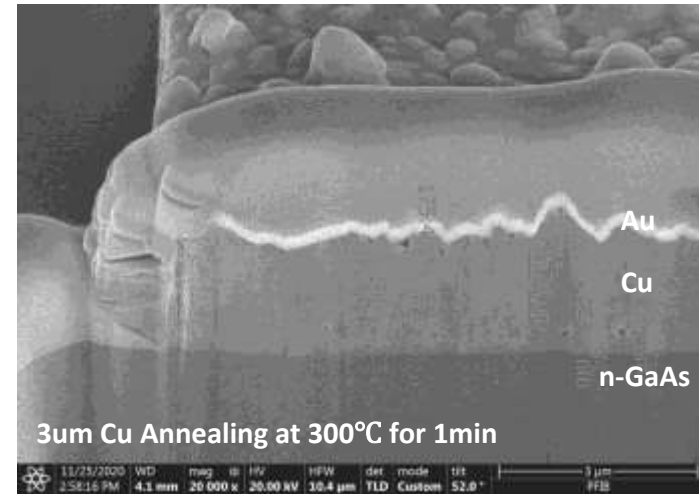


Possible reason:

➤ Defects → Fast route

✗ Additional cleaning process

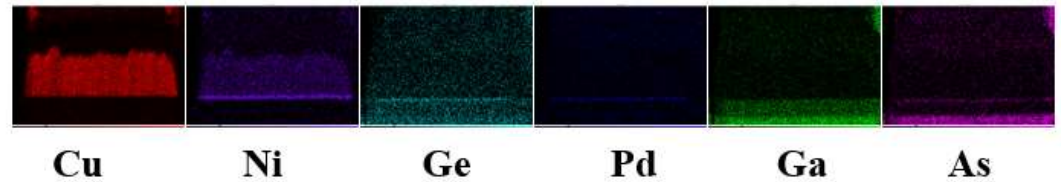
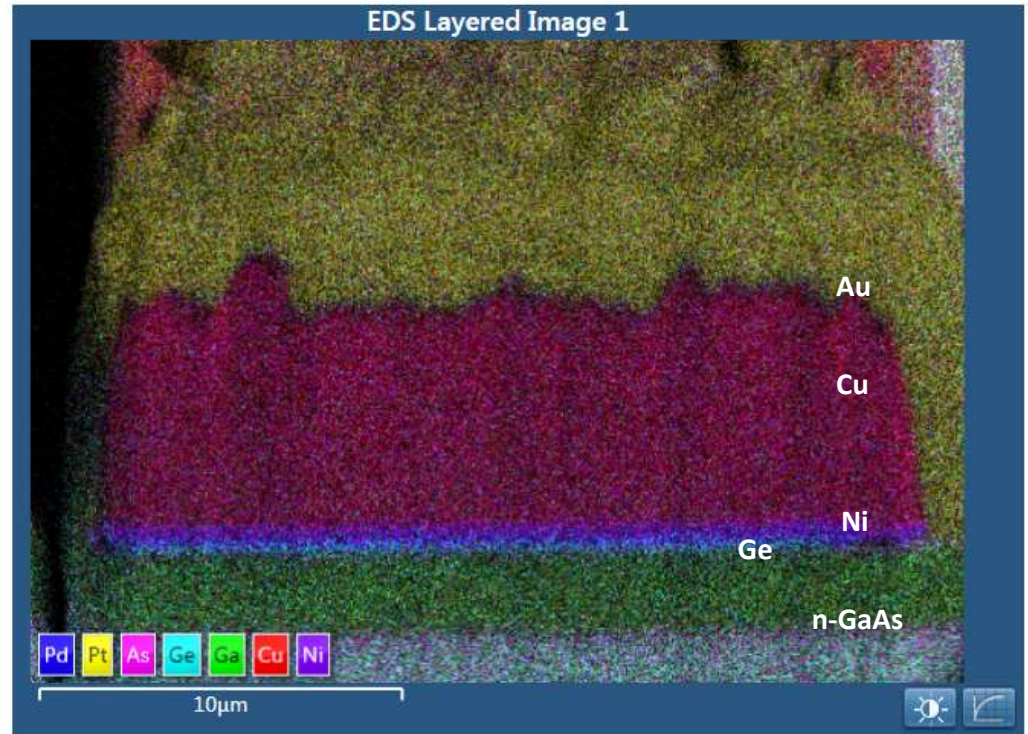
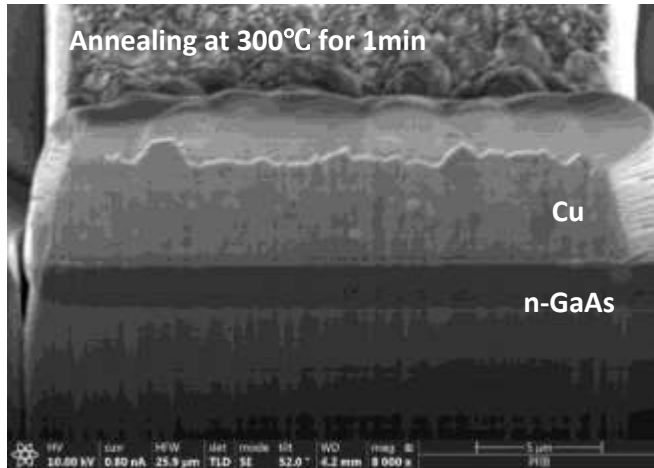
(wet chemical cleaning, plasma etching)



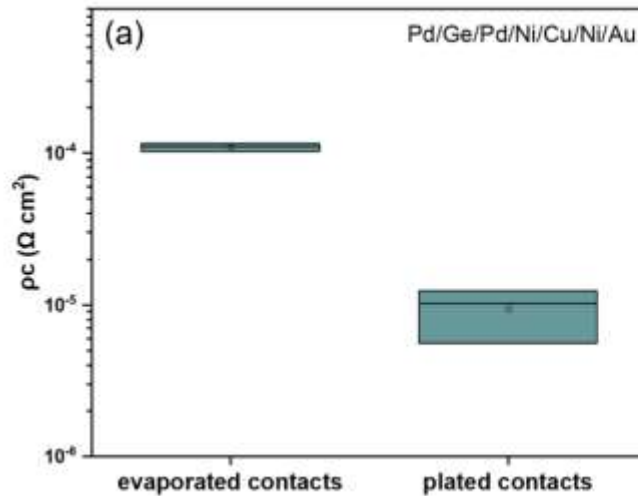
Voids Control

Possible reason:

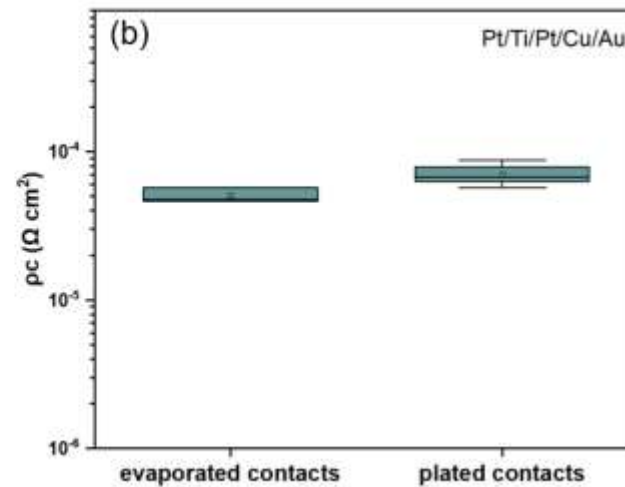
- Kirkendall effect
- Ni seed layer



Specific Contact Resistance



n-GaAs



p-GaAs

Conclusion

Copper can be front contact for GaAs-based III-V solar cells:

- **Pd/Ge/Cu** and **Pt/Ti/Pt/Cu** evaporated metal schemes can achieve a low specific contact resistivities in the order of $10^{-5} \Omega \text{ cm}^2$ and prevent penetration after 30 min tests.
- Unbalanced diffusion rate between Cu and adjacent metal \rightarrow voids, and Ni can reduce Kirkendall effects;
- Specific contact resistance for the **plated contacts** were found similar to or lower than those of the comparative **evaporated contact** structure.

Questions?

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ARENA

Preliminary results for cells

